

## AMENDMENT TRANSMITTAL LETTER

Docket No. 29926/39487

Application No.	Filing Date	Examiner	Art Unit
10/613,331-Conf. #5070	July 3, 2003	Brook Kebede	2823

Applicant(s): In Haeng Lee et al.

Invention:

METHOD FOR FORMING METAL SILICIDE LAYER IN ACTIVE AREA OF

SEMICONDUCTOR DEVICE

#### TO THE COMMISSIONER FOR PATENTS

Transmitted herewith is an amendment in the above-identified application.

The fee has been calculated and is transmitted as shown below.

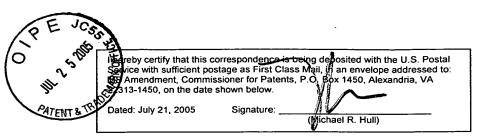
CLAIMS AS AMENDED								
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present		Rate			
Total Claims	28	- 31 =	0	х				
Independent Claims	2	- 3 =	0	x				
Multiple Dependent Claims (check if applicable)								
Other fee (please specify): Extension for response within second month AND Supplemental Information Disclosure Statement						450.00 180.00		
TOTAL ADDITI	IONAL FEE FO	OR THIS AME	NDMENT:			630.00		
x Large Entity					Small Entity			
No additional fee is required for this amendment.								
Please charge Deposit Account No in the amount of \$  A duplicate copy of this sheet is enclosed.								
X A check in the amount of \$ 630.00 to cover the filing fees is enclosed.								
Payment by credit card. Form PTO-2038 is attached.								
x The Director is hereby authorized to charge and credit Deposit Account No13-2855 as described below. A duplicate copy of this sheet is enclosed.								
x Credit any overpayment.								
x Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.								
Michael R. Hul	1 A				Dated:	July 21, 2005		
Attorney Reg. N	lo.: 35,902							
MARSHALL, GI 233 S. Wacker Sears Tower Chicago, Illinois (312) 474-6300	Drive, Suite 63 60606-6357							

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as First Class Mail, in an envelope addressed to: MS Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on the date shown below.

Dated: July 21, 2005

Signature:

(Michael R. Hull)



Docket No.: 29926/39487

(PATENT)

### IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

In Haeng Lee et al.

Application No.: 10/613,331

Confirmation No.: 5070

Filed: July 3, 2003

Art Unit: 2823

For: METHOD FOR FORMING METAL SILICIDE

LAYER IN ACTIVE AREA OF SEMICONDUCTOR DEVICE

Examiner: Brook Kebede

# AMENDMENT IN RESPONSE TO NON-FINAL OFFICE ACTION

MS Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

#### **INTRODUCTORY COMMENTS**

In response to the Office Action dated February 23, 2005, please amend the above-identified U.S. patent application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 9 of this paper.